

ABSTRACT

C Particle Dispersed Fe-Pt-based Sputtering Target

5 Provided is a sputtering target for a magnetic recording film, the sputtering target comprising 5 mol% or more and 60 mol% or less of Pt, 0.1 mol% or more and 40 mol% or less of C, 0.05 mol% or more and 20 mol% or less of titanium oxide, and the remainder being Fe. It is an object of the present invention to provide a high-density sputtering target that can produce a granular magnetic thin film without using any high-cost co-sputtering apparatuses and can also reduce the amount of particles generated during sputtering.

10

Fig. 1